

Amendments to the Specification:

Please replace paragraph beginning at line 23 of ~~page 3~~<sup>pg 2</sup> with the following amended paragraph:

-- As the exposure light has a shorter wavelength, its absorption remarkably increases in a material, and becomes incompatible with use a refraction element or lens for visible light and ultraviolet light. No glass material is compatible with a EUV light's wavelength, and a reflection-type or ~~cataeoptrie~~ catadioptric optical system is used which utilizes only a reflective element or multilayer mirror. A reticule also uses a cataoptric reticle that uses an absorber on a mirror to form a pattern to be transferred. --

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Please replace paragraph beginning at line 26 of page 14 with the following amended paragraph:

-- The mask 120 is a cataoptric reticle, and forms, on a mirror, a circuit pattern (or image) to be transferred. The mask 120 is supported and driven by a mask stage 125. The diffracted light emitted from the mask 120 is projected onto the object 140 after reflected by the projection optical system 130. The mask 120 and object 140 are arranged optically conjugate with each other. Since the exposure apparatus 200 of this embodiment is a scanner, the mask 120 and object 140 are scanned to project a pattern on the mask 120, onto the ~~plate 230~~ object 140. --

Please replace paragraph beginning at line 10 of page 15 with the following amended paragraph:

--The mask stage 125 supports the mask 120 via a reticle chuck 125a, and is connected to a moving mechanism (not shown). The mask stage 125 can use any structure known in the art. The moving mechanism (not shown) includes a linear motor, etc., and moves the mask 120 by